Fig.1

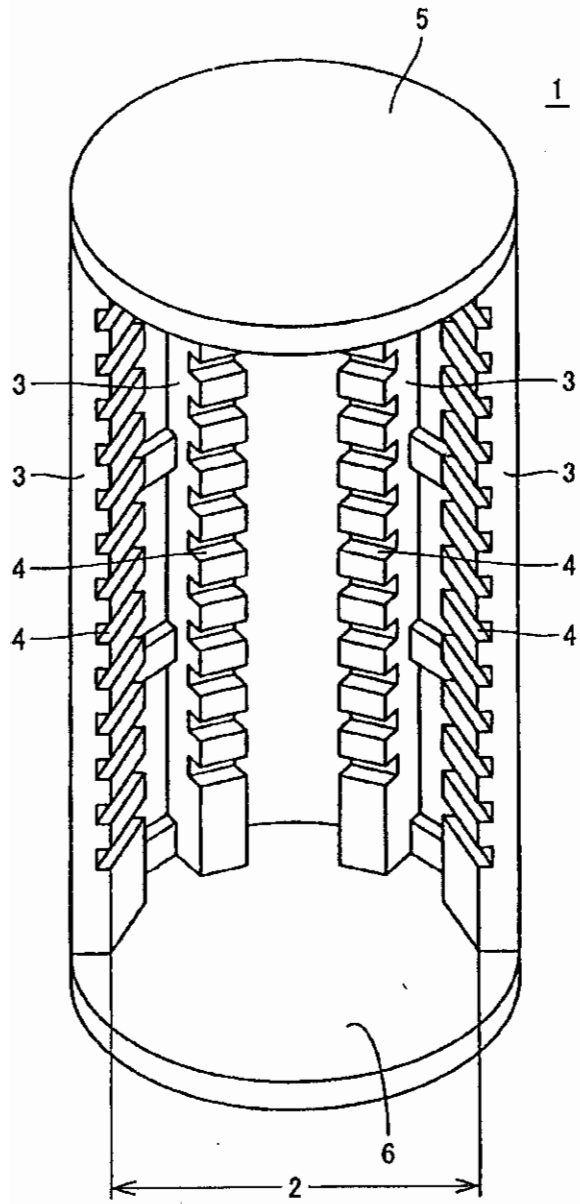


Fig.2

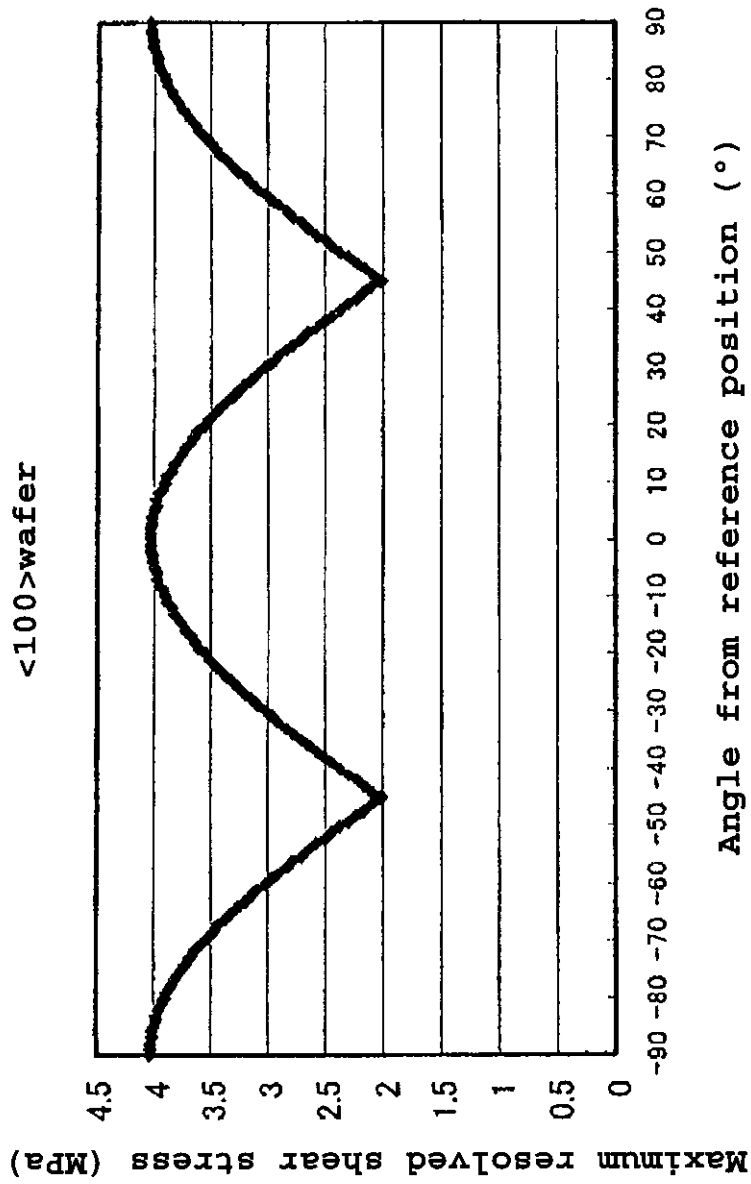

Maximum resolved shear stress (MPa)
4.5
4
3.5
3
2.5
2
1.5
1
0.5
0
-90 -80 -70 -60 -50 -40 -30 -20 -10 0 10 20 30 40 50 60 70 80 90
Angle from reference position (°)
<100>wafer

Fig.3

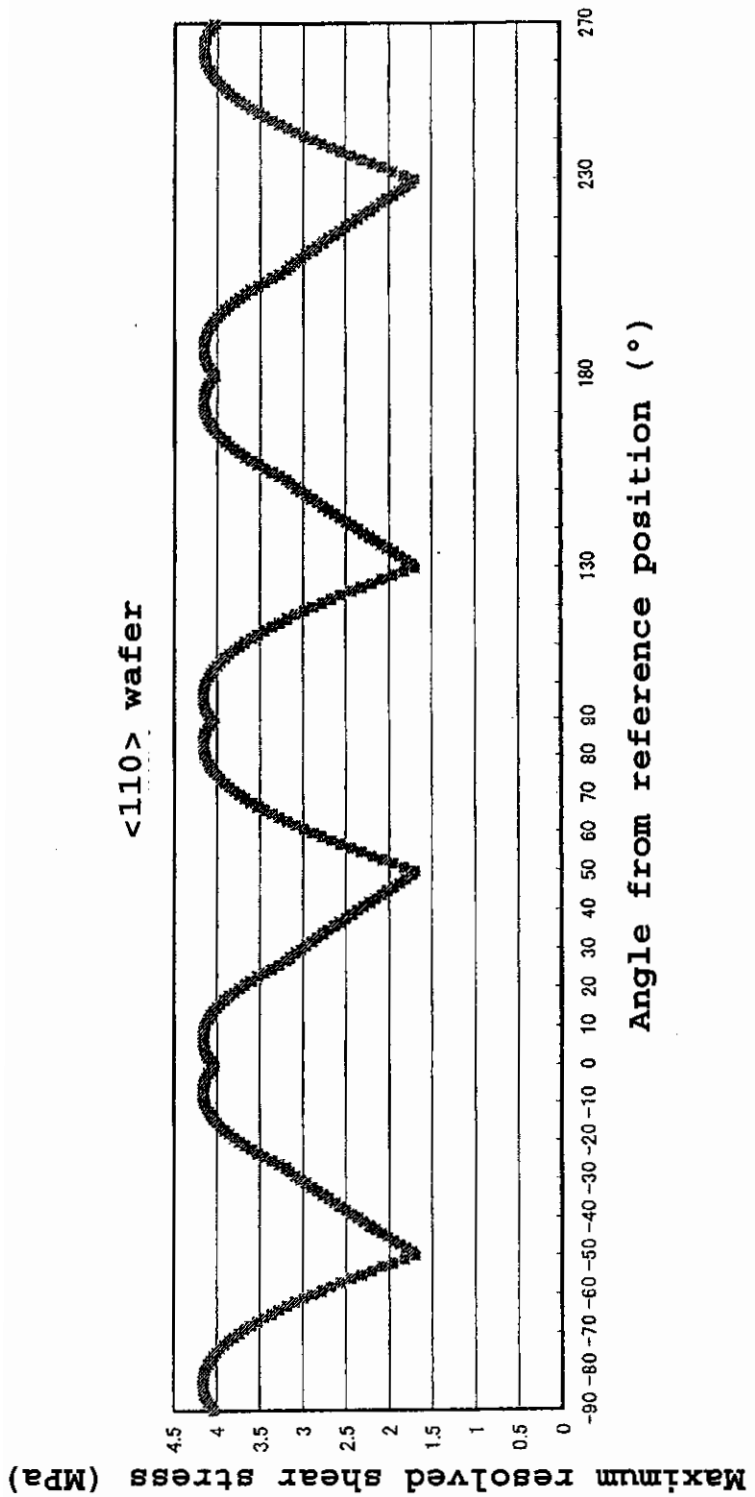

<110> wafer
Maximum resolved shear stress (MPa)
4.5
4
3.5
3
2.5
2
1.5
1
0.5
0
-90 -80 -70 -60 -50 -40 -30 -20 -10 0 10 20 30 40 50 60 70 80 90 130 180 230 270
Angle from reference position (°)

Fig.4

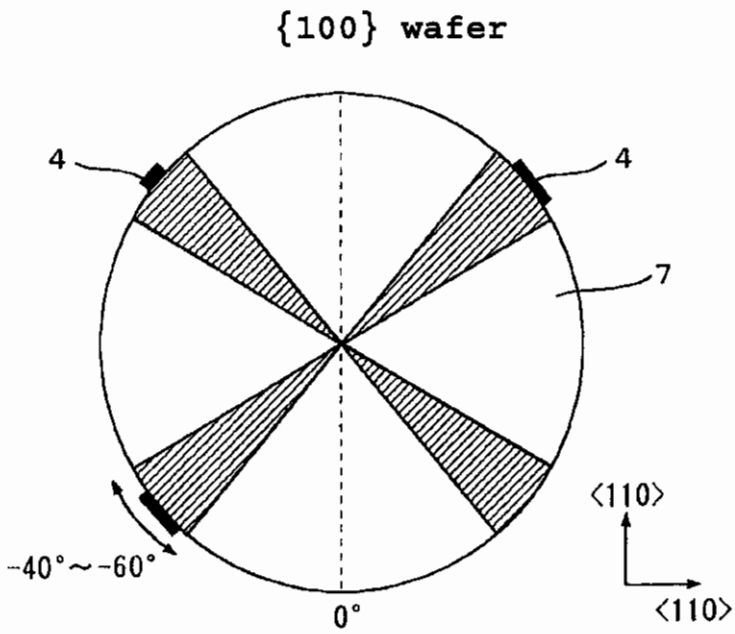


Fig.5

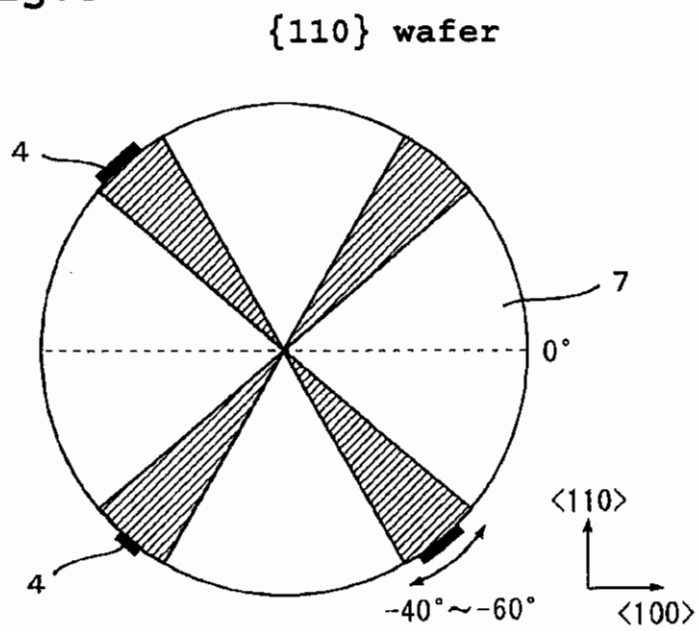


Fig.6

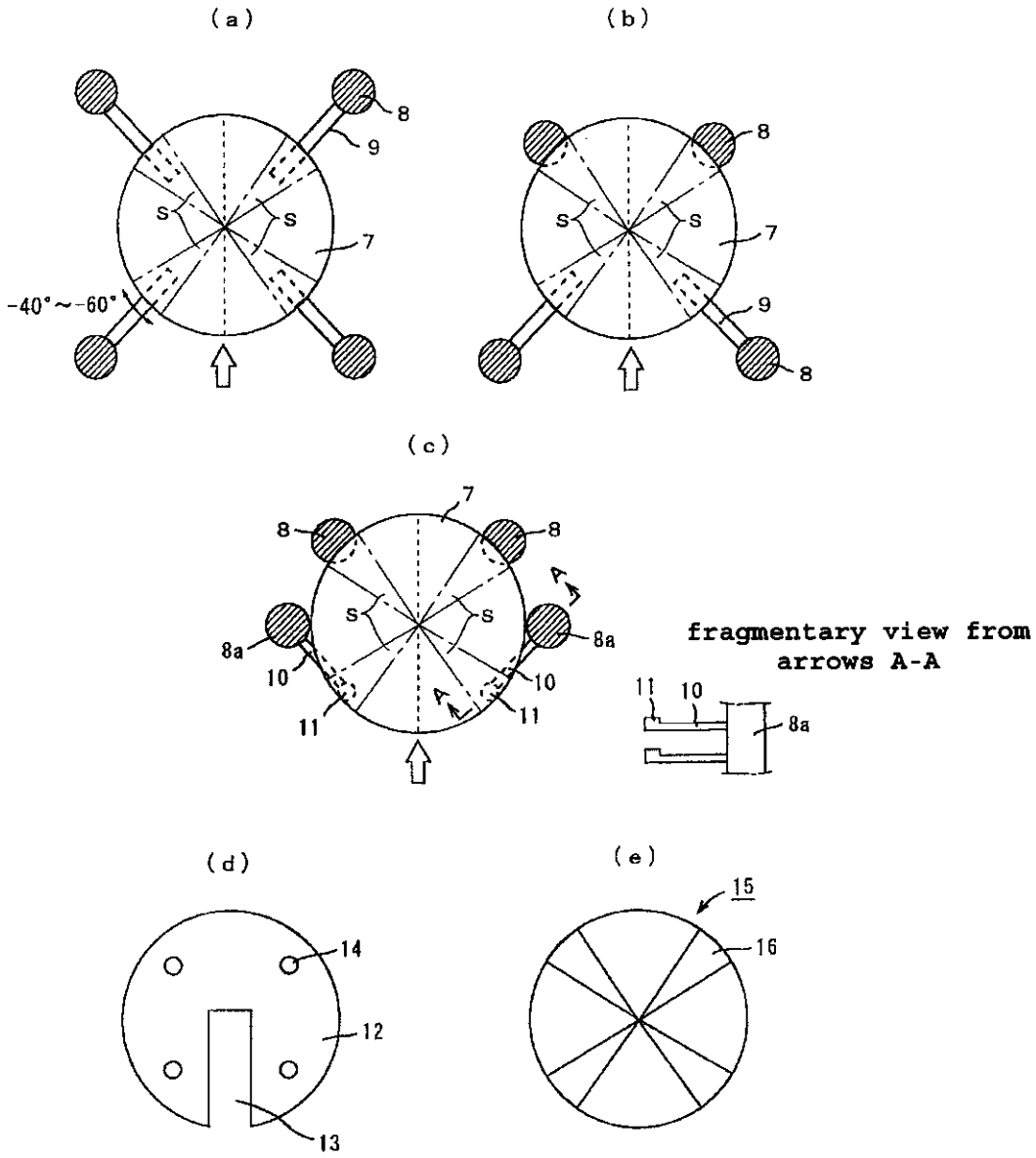
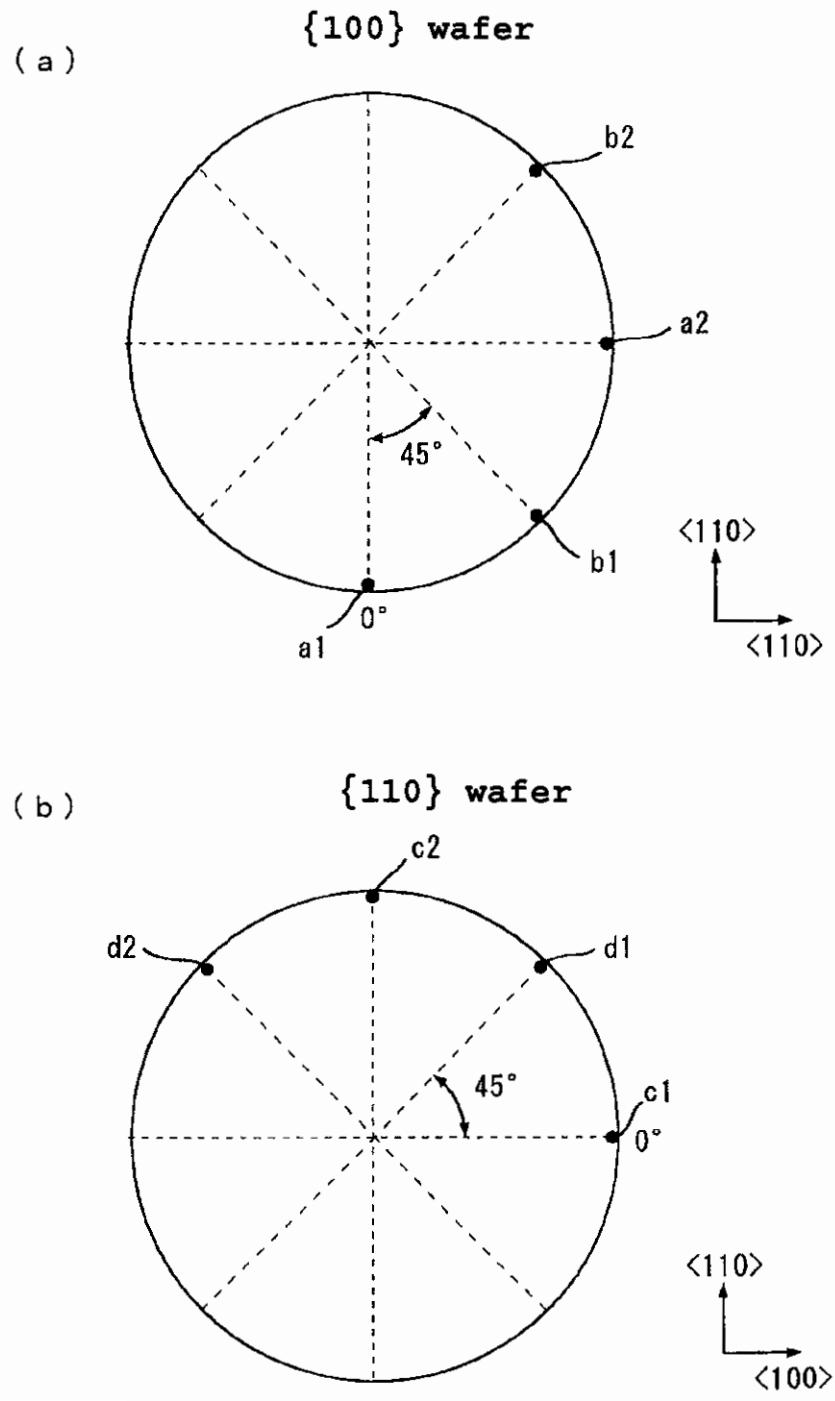

(a)
(b)
(c)
(d)
(e)
8
9
7
S
-40°～-60°
8a
10
11
A
fragmentary view from arrows A-A
14
12
13
15
16

Fig.7


(a)
{100} wafer
b2
a2
45°
b1
0°
a1
<110>
<110>
(b)
{110} wafer
c2
d2
d1
45°
c1
0°
<110>
<100>